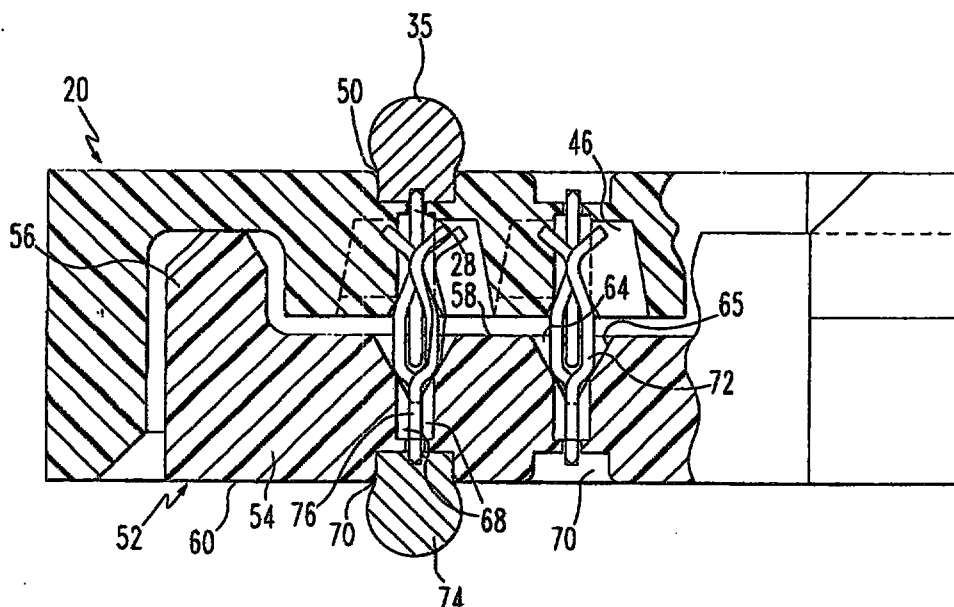




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(54) Title: LOW PROFILE CONNECTOR



(57) Abstract

A low profile board-to-board connector system is disclosed. Retention areas in the respective mating connectors (20, 52) are utilized to receive portions of opposed mating contact terminals (28, 72). Utilization of centralized retention structures allow optimum placement of recessed areas (44, 46) to receive distal portions (82) of mating contact terminals (72). These centralized retention structures (48, 68) also allow maximization of contact beam length in the limited available space, so that favorable contact characteristics are achieved. Contact insertion/retention features are positioned at intermediate locations of the contact beams, for enhanced contact retention and improved beam performance. Terminal contacts may be retained in a passage by projections (48, 68) that engage openings (96) formed in the retention portion of the contact terminal.